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Form PTO-1449 (modified)				Atty. Docket N 102-0102US	Atty. Docket No. 102-0102US		Serial No.	
List of Patents and Publications for Applicant's INFORMATION DISCLOSURE STATEMENT				Inventor/Applicant: Neal R. Rueger / Micron Technology, Inc.  Title: IMPROVED INDUCTIVELY COUPLED PLASMA CHAMBER ATTACHABLE TO A PROCESSING CHAMBER FOR ANALYSIS				
				OF PROCESS GASES Filing Date: Group:				
(Use several sheets if necessary)				herewith	1		unk	
U.S. Patent Documents								
Exam. Init.	Ref. Des.	Document Number	Date	Name	Class	Sub Class	Filing Date of App.	
	A1							
Foreign Patent Documents								
Exam. Init.	Ref. Des.	Document Number	Date	Country	Class	Sub Class	Translation Yes/No	
	<b>B</b> 1						7	
(	Other A	Art (Includir	ng Author	, Title, Date	Pertine	nt Page	es, Etc.)	
Exam. Init.	Ref. Des.	Citation						
$\sim$	CI	Bladimiro Ruiz, Jr. & Herbert E. Litvak, "Investigation of Silicon Trench Etch Chemistry Using a Downstream Chemical Monitor," 4th AVS Int'l Conference on Microelectronics and Interfaces (2003)						
~	C2	Freddy Gaboriau et al., "Langmuir Probe Measurements in an Inductively Coupled Plasma:," J. Vac. Sci. Technol., Vol. A20(3), pp. 919-27 (May/Jun 2002);						
7	C3	M.V. Malyshev et al., "Diagnostic Studies of Aluminum Etching in an Inductively Coupled Plasma System:," J. Vac. Sci. Technol., Vol. A18(3), pp. 849-59 (May/Jun 2000)						
7	C4	D.M. Manos et al., "Characterization of Laboratory Plasmas With Probes," J. Vac. Sci. Technol., Vol. A3(3), pp. 1059-66 (May/Jun 1985)						
Y	C5	S.M. Rossnagel et al., "Langmuir Probe Characterization of Magnetron Operation," J. Vac. Sci. Technol., Vol. A4(3), pp. 1822-25 (May/Jun 1986)						
$\sim$	C6	V. Kaeppelin et al., "Ion Energy Distribution Functions and Langmuir Probe Measurements in Low Pressure Argon Discharges," J. Vac. Sci. Technol., Vol. A20(2), pp. 526-29 (Mar/Apr 2002)						
~	C7	Terry A. Miller, "Optical Emission and Laser-Induced Fluorescence Diagnostics," J. Vac. Sci. Technol., Vol. A4(3), pp. 1768-72 (May/Jun 1986)						
Examiner: Rame Date Considered: 6/9/06								
EXAMINER: INITIAL IF REFERENCE CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED. INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.								

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List of Patents and Publications for Applicant's	Inventor/Applicant: Neal R. Rueger / Micron Technology, Inc.		
INFORMATION DISCLOSURE STATEMENT		·	
	Title: IMPROVED INDUCTIVELY COUPLED		
,	PLASMA CHAMBER ATTACHABLE TO A		
	PROCESSING CHAMBER FOR ANALYSIS		
	OF PROCESS GASES		
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(Ose several sheets it necessary)	herewith	unk	

## Other Art (Including Author, Title, Date Pertinent Pages, Etc.)

Exam. Init.	Ref. Des.	Citation		
Y		V.M. Donnelly, "A Simple Optical Emission Method for Measuring Percent Dissociations of Feed Gases in Plasmas:," J. Vac. Sci. Technol., Vol. A14(3), pp. 1076-87 (May/Jun 1996)		
~	С9	A.D. Kuypers et al., "Emission Spectroscopy and Actinometry in a Magnetized Low Pressure Radio Frequency Discharge," J. Vac. Sci. Technol., Vol. A8(5), pp. 3736-45 (Sep/Oct 1990)		
~	C10	Zhimin Wan et al., "Electron Cyclotron Resonance Plasma Reactor for SiO <sub>2</sub> Etching:," J. Vac. Sci. Technol., Vol. A13(4), pp. 2035-43 (Jul/Aug 1995)		
	C11			

Examiner:	Rang	DATE CONSIDERED:	6/9/06